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Vishnu K. AgarwalPriority FILING DATE  
August 31, 2000Priority GROUP  
2813

## U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
YH	AA	6,180,481	01/2001	Deboer et al			
	AB	6,218,256	04/2001	Agarwal			
	AC	6,104,049	08/2000	Solayappan et al			
	AD	6,180,447	01/2001	Park et al			
	AE	6,274,428	08/2001	Wu			
	AF	6,124,158	09/2000	Dautartas et al			
	AG	6,144,060	11/2000	Park et al			
	AH	5,316,982	05/1994	Taniguchi			
	AI	6,281,142	06/1999 05/2001	Basceri et al			
	AJ	6,204,172	09/1996 03/2001	Marsh			
	AK	5,432,732	07/1995	Ohmi			
	AL	6,242,299	06/2001	Hickert			
	AM	6,249,056	06/2001	Kwon			
	AN	6,291,289	09/2001	Rhodes			
YH	AO	6,174,770	01/2001	Chi			

## FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AP							
	AQ							

## OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

YH	AR		A.W. Ott, et al., "Atomic Layer Controlled Deposition of Al <sub>2</sub> O <sub>3</sub> Films Using Binary Reaction Sequence Chemistry", Applied Surface Science (107), 1996, pps. 128-136.
	AS		

EXAMINER

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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

NR  
5-31-7